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APPLICATION NO.		ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOC:KET NO.	CONFIRMATION NO.
09/696,232		10/26/2000	Mitsuru Ishikawa	07553.0017	5127
22852	7590	05/26/2005		EXAM	INER
	N, HENI	DERSON, FARAI	BOW, GARRETT & DUNNER	OLSEN, A	LLAN W
LLP 901 NEW Y	ORK AV	ENUE, NW	ART UNIT	PAPER NUMBER	
WASHINGT	ON, DC	20001-4413		1763	

DATE MAILED: 05/26/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)
		09/696,232	ISHIKAWA ET AL.
	Office Action Summary	Examiner	Art Unit
		Allan Olsen	1763
	The MAILING DATE of this communication app	ears on the cover sheet	with the correspondence address
	od for Reply		
	A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	within the statutory minimum of till apply and will expire SIX (6) M cause the application to become	a reply be timely filed thirty (30) days will be considered timely. ONTHS from the mailing date of this communication. ABANDONED (35 U.S.C. § 133).
	1) Responsive to communication(s) filed on <u>02 D</u>	<u> December 2003</u> .	
2	a) This action is FINAL . 2b)⊠ Thi	s action is non-final.	
	Since this application is in condition for allowa closed in accordance with the practice under the		
Dis	position of Claims		
	4)⊠ Claim(s) <u>1-5,14 and 17</u> is/are pending in the a		
	4a) Of the above claim(s) is/are withdraw	vn from consideration.	
	5) Claim(s) is/are allowed.		
	6)⊠ Claim(s) <u>1-5,14 and 17</u> is/are rejected.		
	7) Claim(s) is/are objected to.		
	8) Claim(s) are subject to restriction and/or lication Papers	election requirement.	
	9) \square The specification is objected to by the Examiner		
1	D) $igotimes$ The drawing(s) filed on $\underline{\it 18 March 2003}$ is/are: a)⊠ accepted or b)⊡ obje	ected to by the Examiner.
	Applicant may not request that any objection to the	drawing(s) be held in abo	eyance. See 37 CFR 1.85(a).
1	 The proposed drawing correction filed on 	is: a)☐ approved b)☐	disapproved by the Examiner.
	If approved, corrected drawings are required in rep	•	
1	2)☐ The oath or declaration is objected to by the Exa	aminer.	
Pric	rity under 35 U.S.C. §§ 119 and 120		·
1	3)⊠ Acknowledgment is made of a claim for foreign	priority under 35 U.S.C	C. § 119(a)-(d) or (f).
	a)⊠ All b)□ Some * c)□ None of:		•
	1. Certified copies of the priority documents	s have been received.	
	2. Certified copies of the priority documents	s have been received in	Application No
	 3. Copies of the certified copies of the prior application from the International Bur * See the attached detailed Office action for a list of the prior application. 	eau (PCT Rule 17.2(a)).
14) Acknowledgment is made of a claim for domestic	•	
	a) ☐ The translation of the foreign language pro 5)☐ Acknowledgment is made of a claim for domesti	visional application has	been received.
	hment(s)	o priority under 00 0.3.	C. 33 120 diluior 121.
1) [2) [Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Dráwing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449) Paper No(s)	5) Notice	ew Summary (PTO-413) Paper No(s) of Informal Patent Application (PTO-152)

U.S. Patent and Trademark Office PTO-326 (Rev. 04-01)

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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on March 15, 2005 has been entered.

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claim 17 is rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the enablement requirement. The claims contains subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention. The claim requires that "a temperature of a bottom portion of the contact holes is maintained at about –20° C, a temperature of an opening portion of the contact holes is maintained at about 30° C, and a temperature of a sidewall portion of the contact holes is maintained at about 50° C", however, the specification provides no guidance as to how one is to obtain such a temperature profile.

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Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-3, 5 and 14 are rejected under 35 U.S.C. 102(b) as being anticipated by US Patent 5,658425 issued to Halman et al. (hereinafter, Halman). Halman teaches using a plasma comprising CF_4 , Ar and N_2 to etch a multi-layered oxide. Halman teaches the multilayered oxide may comprise a BPSG (Halman's layer 5) with an overlying layer of TEOS (Halman's layer 8) which corresponds to Applicant's claimed organic film containing Si. Halman teaches the multilayered oxide may also comprise an overlying layer of a planarizing spin-on-glass. Halman provides examples in which the amount of N_2 is less than the amount of CF_4 , however, Halman teaches that an unlimited amount of N_2 may be used. See: abstract; column 4, lines 18-21, 35-41 and 50-53; and column 5, lines 8-12.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claim 4 is rejected under 35 U.S.C. 103(a) as being unpatentable over Halman as applied to claim 1 above, and further in view of US Patent 5,721,156 issued to Matsuura (hereinafter, Matsuura).

Halman does not teach that the Si-containing organic layer is a polysiloxane.

Matsuura teaches forming a TEOS derived polymeric layer. Matsuura teaches that a polysiloxane can be used in place of the TEOS layer.

It would have been obvious to one skilled in the art to use a polysiloxane because in semiconductor fabrication processes TEOS layers are generally polymeric layers that are derived from TEOS and these TEOS derived polymeric layers typically comprise polysiloxane. Alternatively, it would have been obvious to use a polysiloxane because Matsurra teaches that a TEOS derived layer and a polysiloxane layer are functionally equivalent.

Response to Arguments

Applicant's arguments filed March 15, 2005 have been fully considered but they are not persuasive. Applicant argues that the disclosure does not lack enablement because it was well known in the art how to achieve and maintain temperature gradients within contact holes.

In reply, it is noted that the results of a search carried out by the examiner for etching while maintaining a contact hole temperature gradient do not suggest that this feature is well known, especially for maintaining the claimed temperature profile wherein the bottom of the hole is at –20°C while the middle is at 50°C and the top is at 30 °C.

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Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Allan Olsen whose telephone number is 571-272-1441. The examiner can normally be reached on M-F 1-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on 571-272-1435. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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Allan Olsen Primary Examiner Art Unit 1763